

***LCMO***

***From thin films to nanowires***

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Groupmeeting 08-09-05

# Outline

## ✓ Introduction

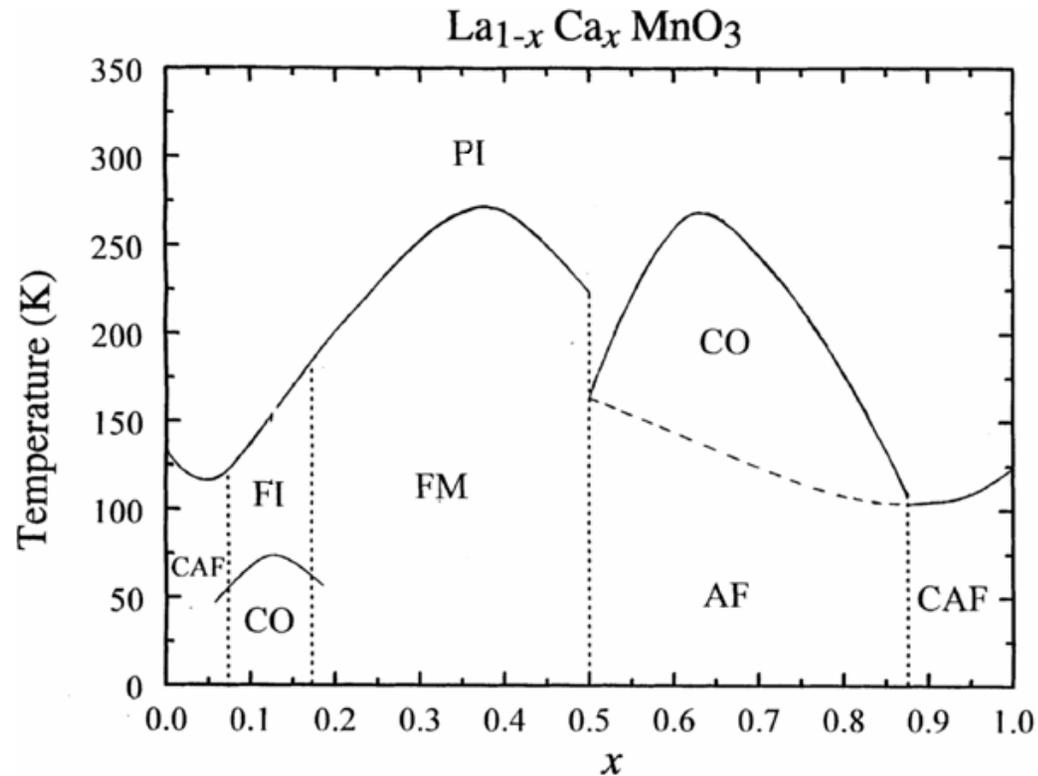
- Complex phase diagram
- Double exchange
- Magnetoresistance

## ✓ Miscut substrates

## ✓ Growing LCMO nanowires

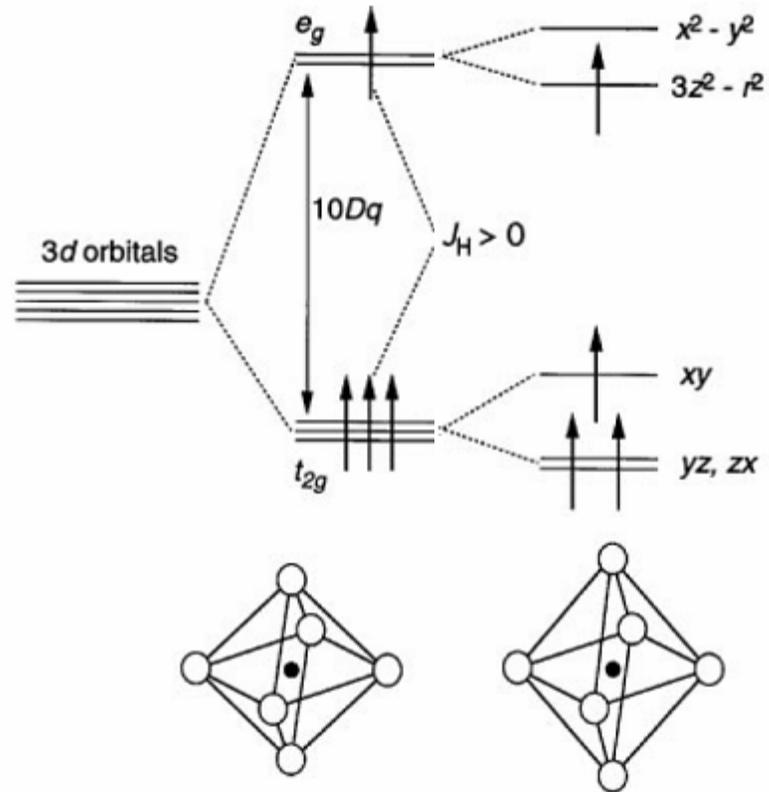
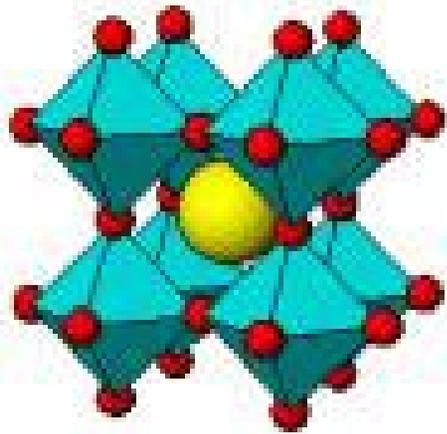
- Sol-gel process with alumina templates
- Pt as contact material

# LCMO



- $\text{La}_{0.7}\text{Ca}_{0.3}\text{MnO}_3$  : - CMR effect  
- 100% polarized ferromagnet  
- metal-insulator transition

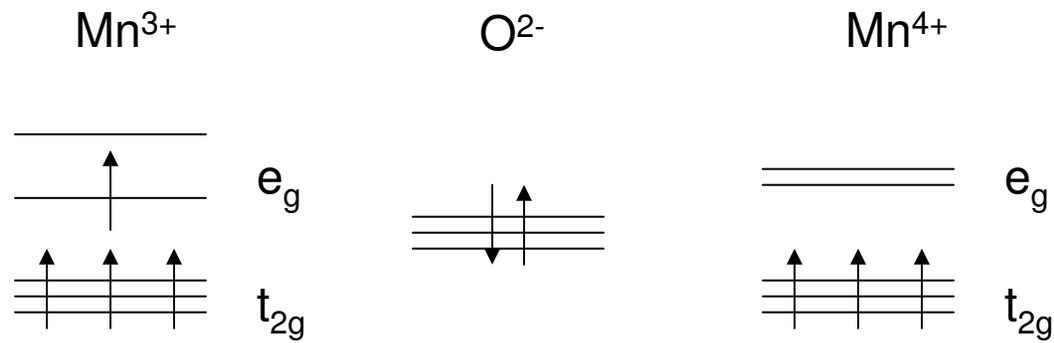
# Perovskite lattice



$t_{2g}$ : localized core electrons

$e_g$ : delocalized electron

# Double exchange



Hopping mediates the onset of the ferromagnetic state

# Double exchange

Hopping rate determined by:

Transfer integral

$$\tilde{t} = t \cos(\Delta\theta_s / 2)$$

$\Delta\theta_s$ : difference in spin angle between the Mn ions

One electron bandwidth

$$W \propto \frac{\cos^2(\theta)}{l_{Mn-O}^{3.5}}$$

$\theta$ : Mn-O-Mn bond angle,  $l_{Mn-O}$ : Mn-O bond length

# Jahn Teller distortions

DE model does not explain the localization above  $T_C$

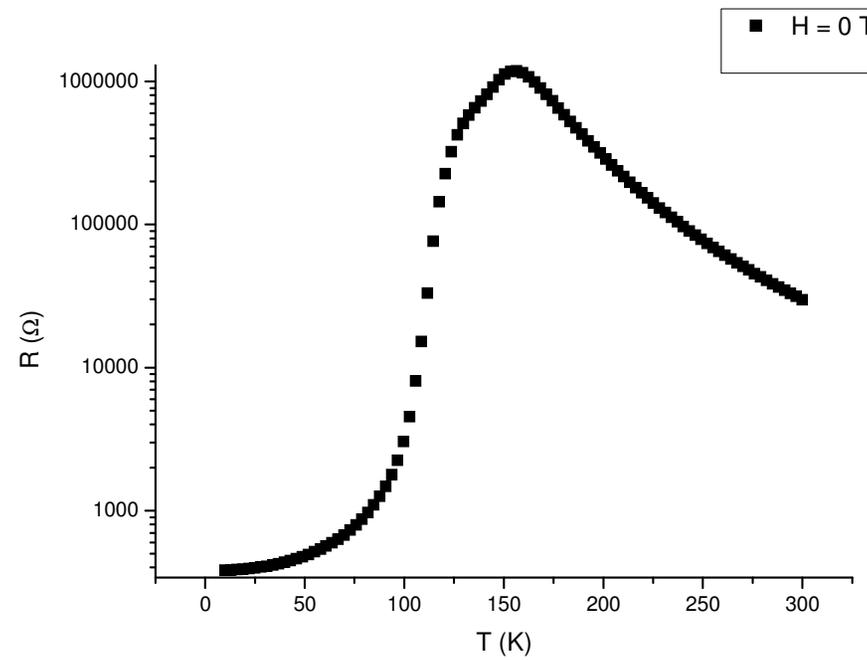
Strong electron-lattice coupling can cause localization

Competition between polaron formation and delocalization due to hybridization which can be described by the ratio,

$$\lambda = \frac{E_{latt}}{t_{eff}}$$

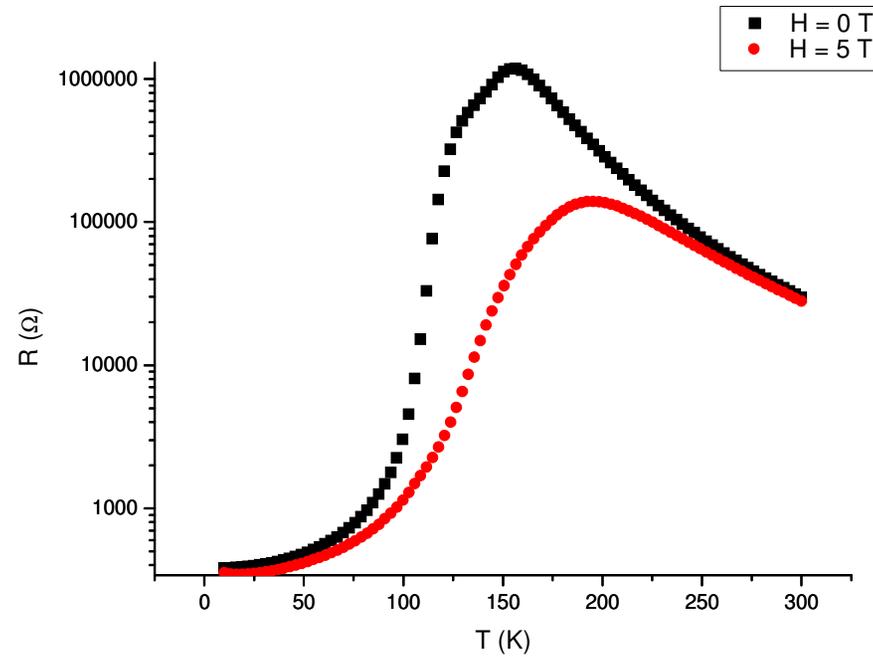
$t_{eff}$ : 'bare' electron kinetic energy,

$E_{latt}$ : energy gained by e-ph coupling without hybridization

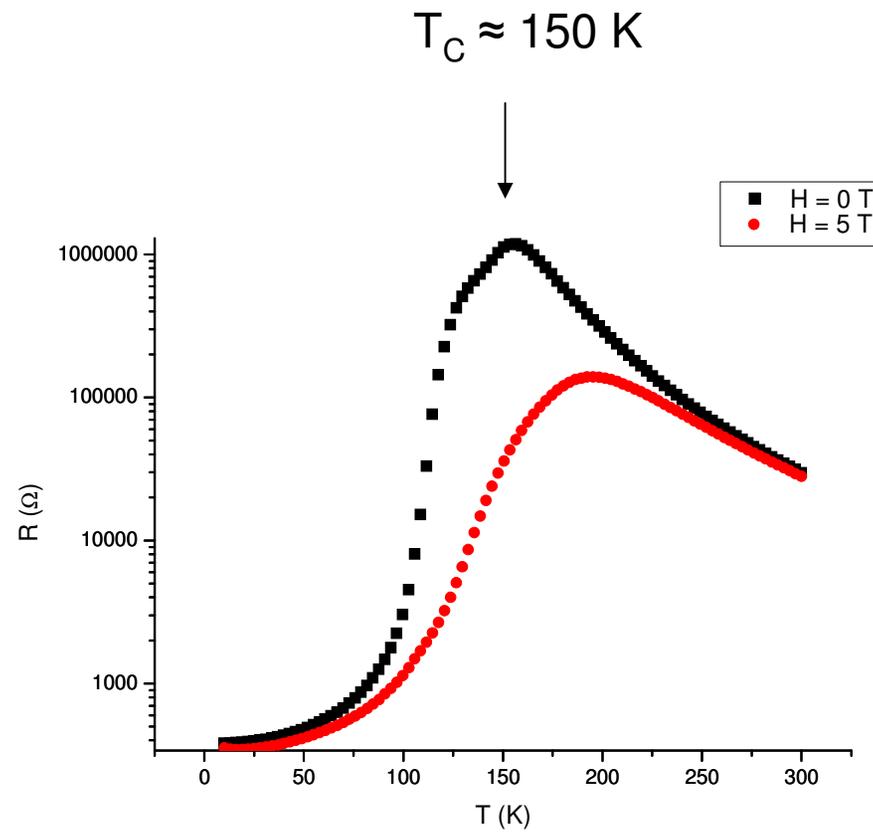


Above  $T_C$  : activated polaron hopping

Below  $T_C$  :  $e_g$  electrons delocalize, onset of spin ordering



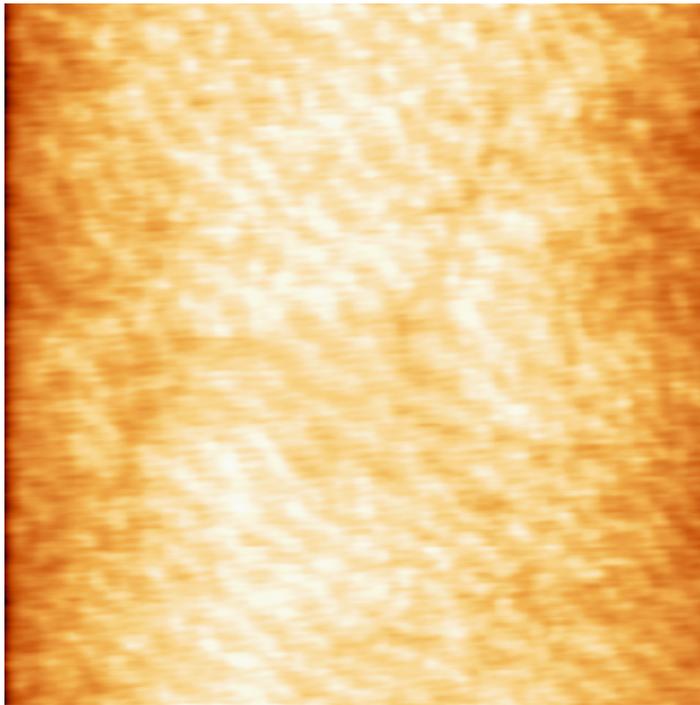
External field : different magnetic domains align reducing resistance, CMR effect



Bulk :  $T_C \approx 270 \text{ K} \rightarrow$  lattice mismatch with STO substrate causes strain which reduces  $T_C$

# Miscut substrates

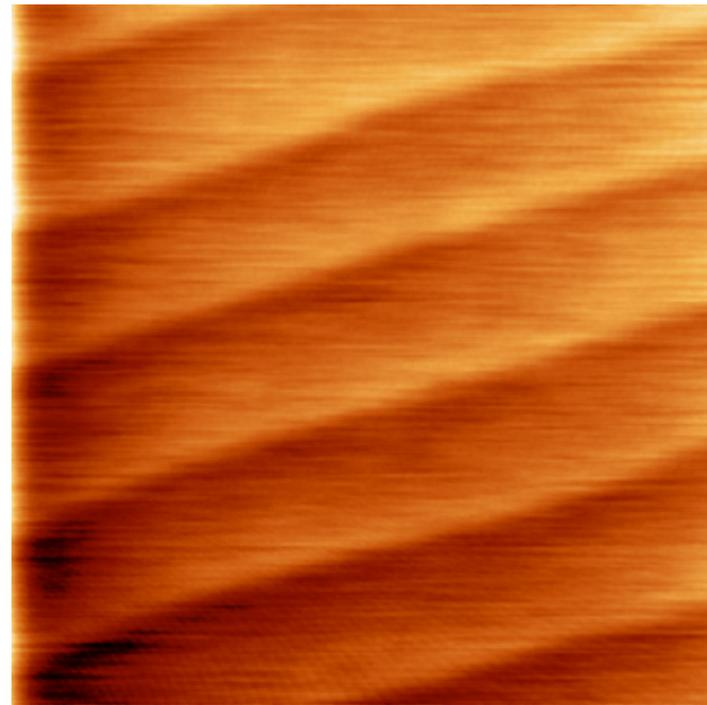
AFM picture of  $0.2^\circ$  miscut substrate



← 2.3 x 2.3  $\mu\text{m}$  →

No visible steps

AFM picture of  $0.18^\circ$  miscut substrate terminate layer  $\text{TiO}_2$

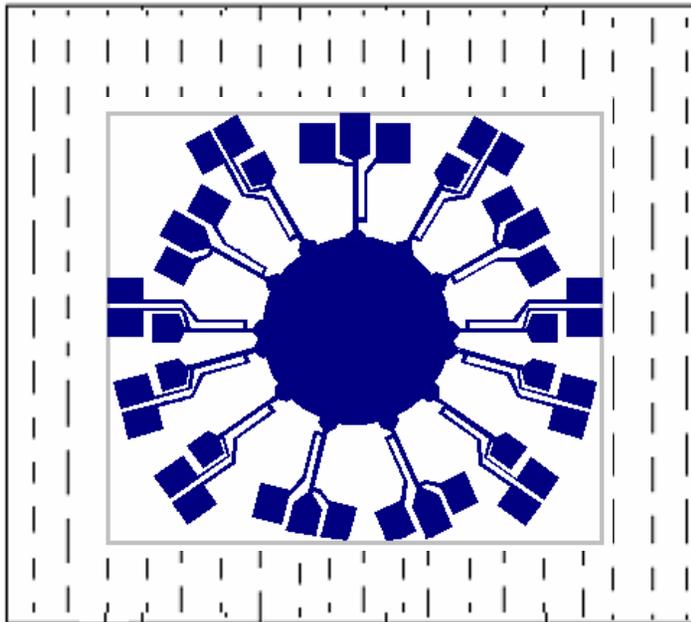


← 737 x 737 nm →

Clearly visible steps

# Miscut substrates

Optical lithography



Structure sizes:

Diameter:  $\sim 5$  mm

Contactpads:  $\sim 350 \times 400$   $\mu\text{m}$

Strips:  $w = \sim 40$   $\mu\text{m}$   
 $l = \sim 500$   $\mu\text{m}$

$T_C$  reduction:

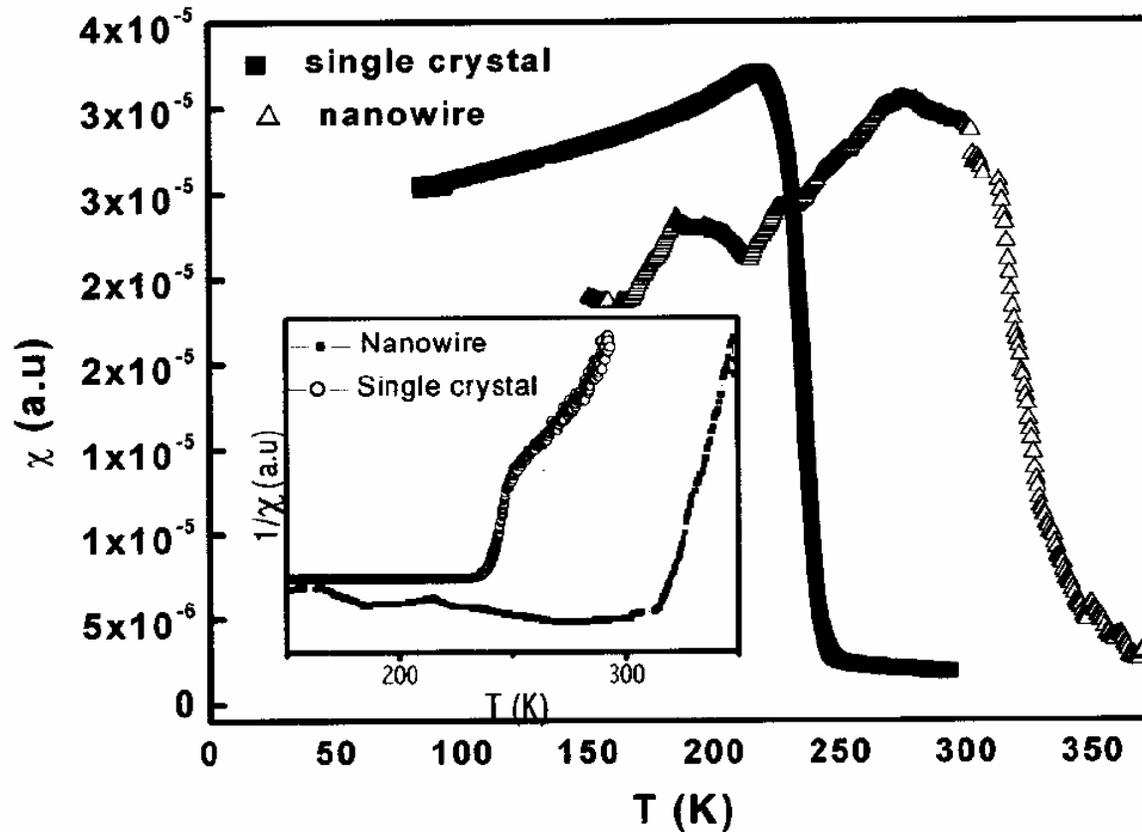
- ✓ Strain due to lattice mismatch with substrate
- ✓ Internal “chemical” pressure: decrease radius dopant ions

$T_C$  enhancement:

- ✓ External pressure: oxygen ions more densely packed
- ✓ Reduction of sample size: nanopowders & nanowires

# LCMO nanowires

Shankar et al. Appl. Phys. Lett., Vol. 84, No. 6, 9 February 2004

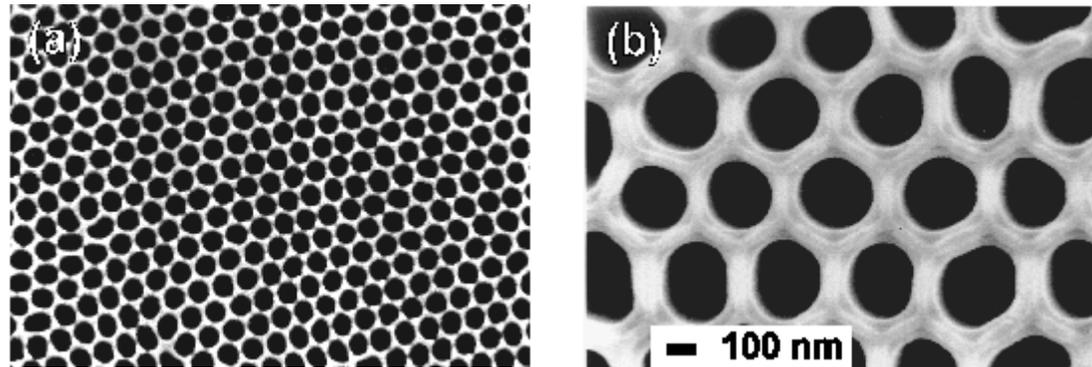


Nanowire:  $T_C$  is enhanced compared to bulk single crystal

# LCMO nanowires

Growth process: Sol-gel

Polymer assisted nucleation of cation complex in pores of alumina templates



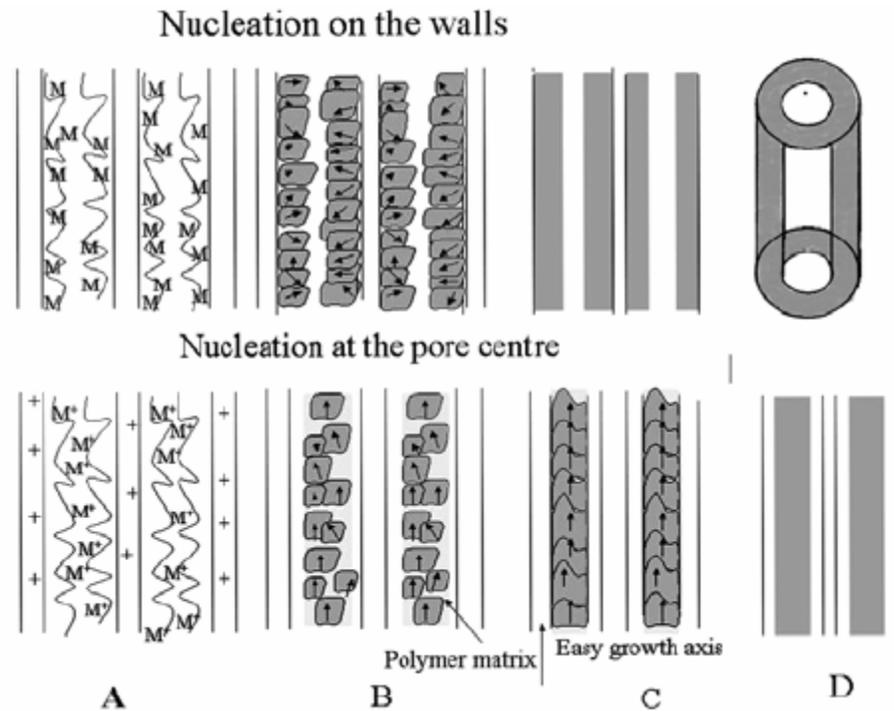
Sol:  $\text{La}_2\text{O}_3$ ,  $\text{CaCO}_3$ ,  $\text{Mn}(\text{NO}_3)_2$  & ethylene glycol

# LCMO nanowires

Shankar et al. nanotech., Vol. 15, 1312, 2004

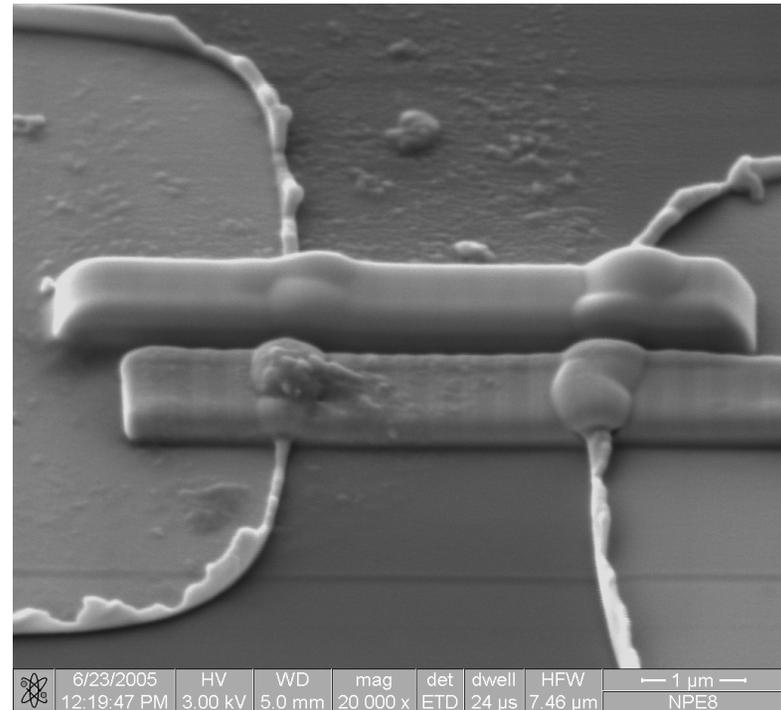
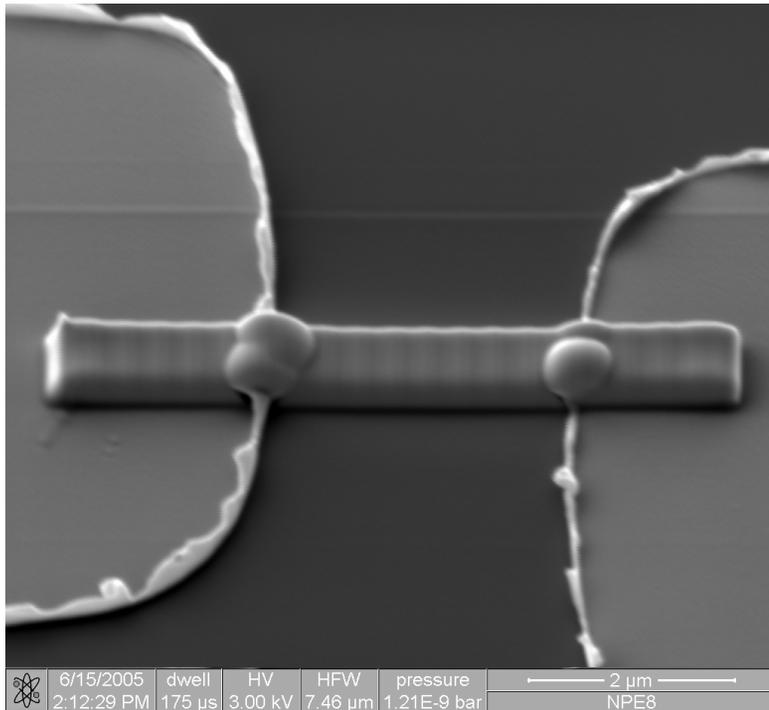
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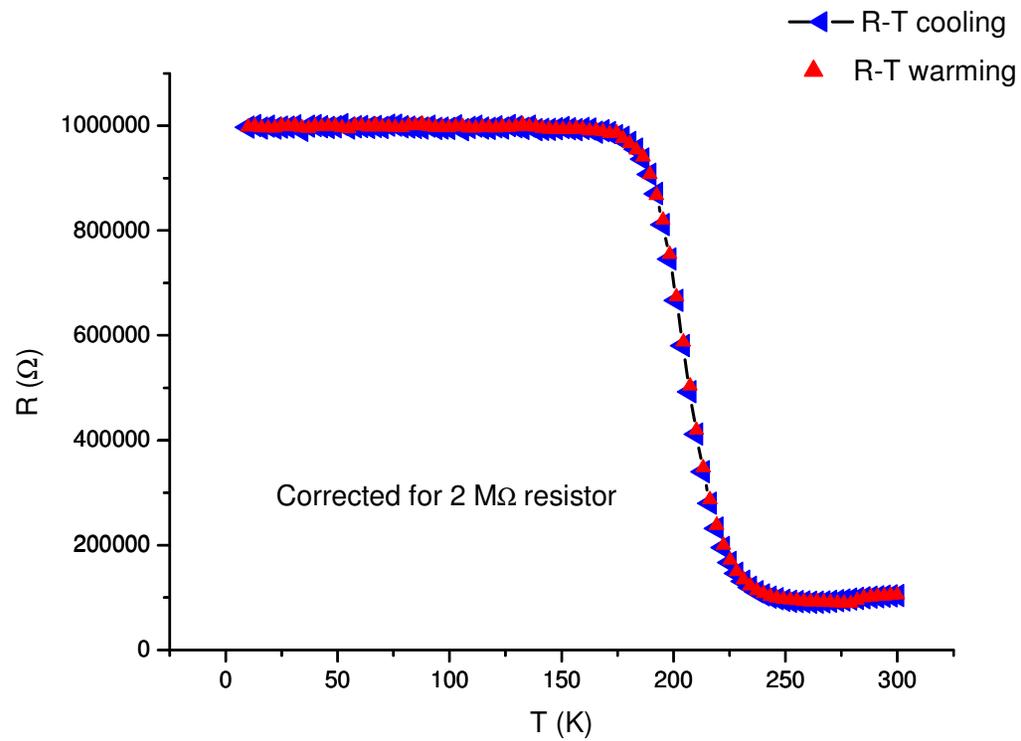
# Pt as a contact material

Contact geometry can be written with FEI nanosem

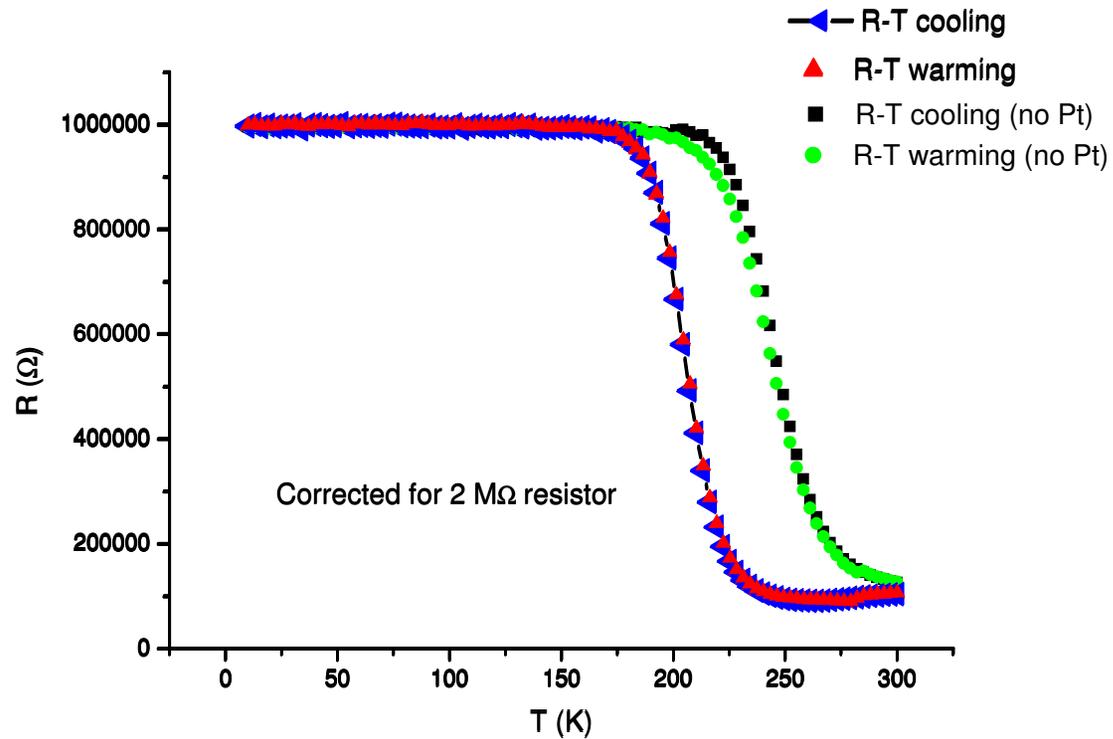


Pt strip:  $t = 500 \text{ nm}$   
 $w = 800 \text{ nm}$   
 $l = 6.5 \text{ μm}$

# Pt as a contact material



# Pt as a contact material

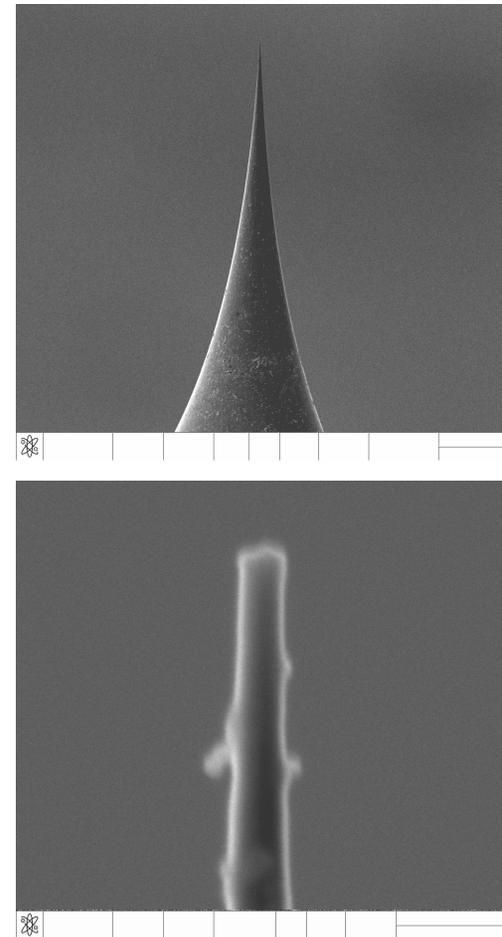
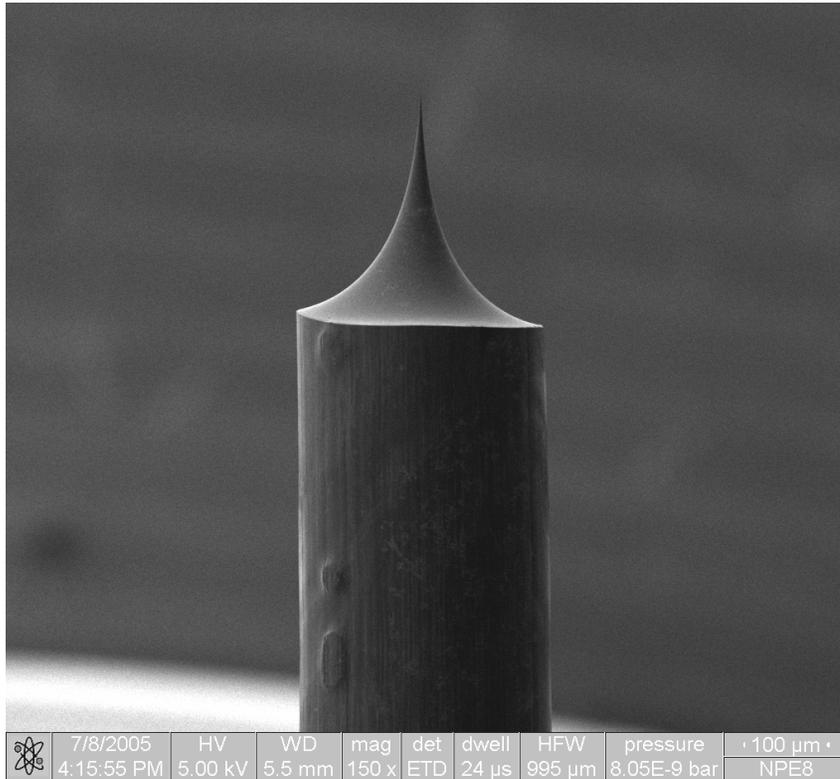


Measuring substrate instead of Pt strip

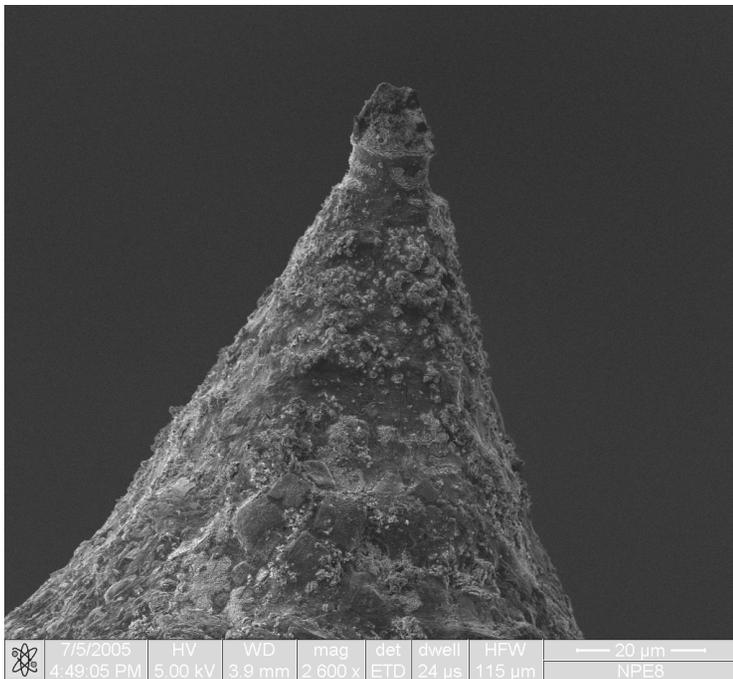
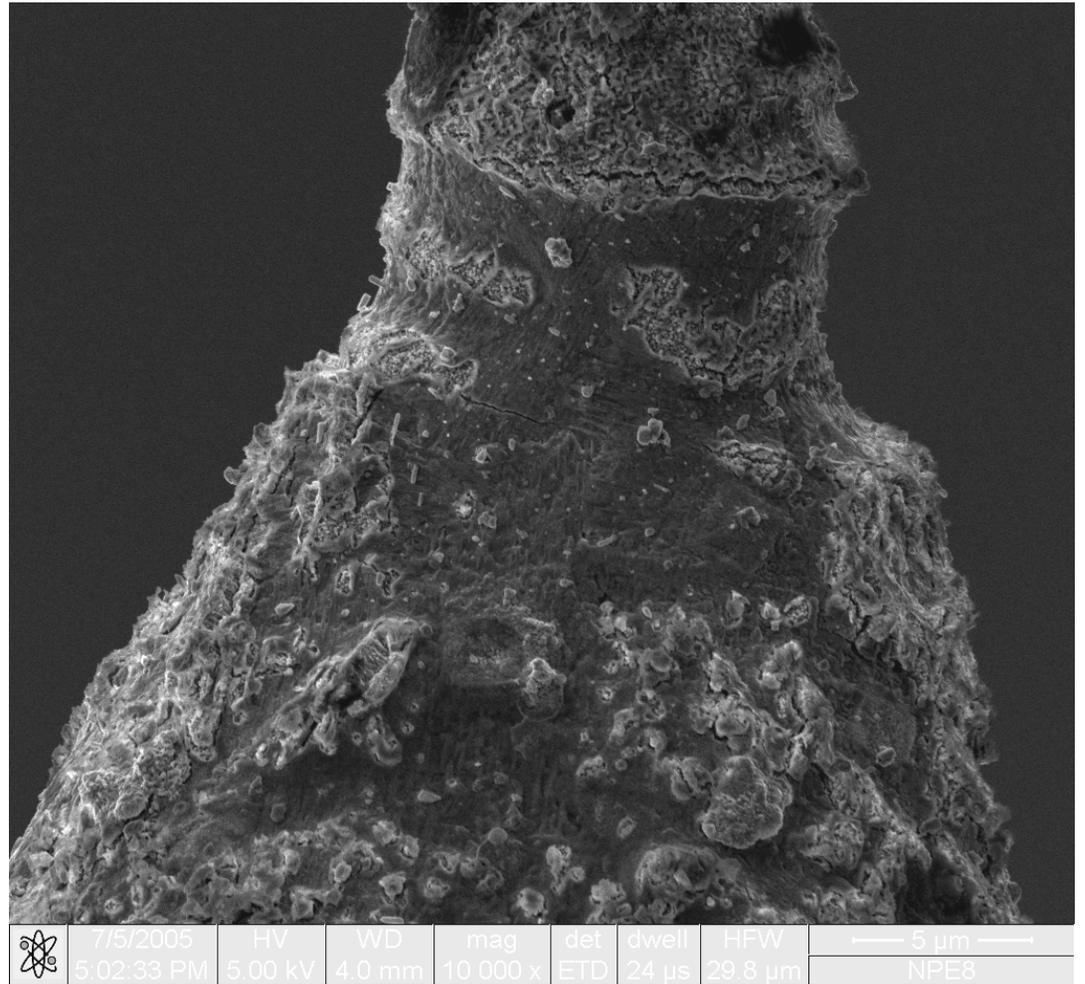
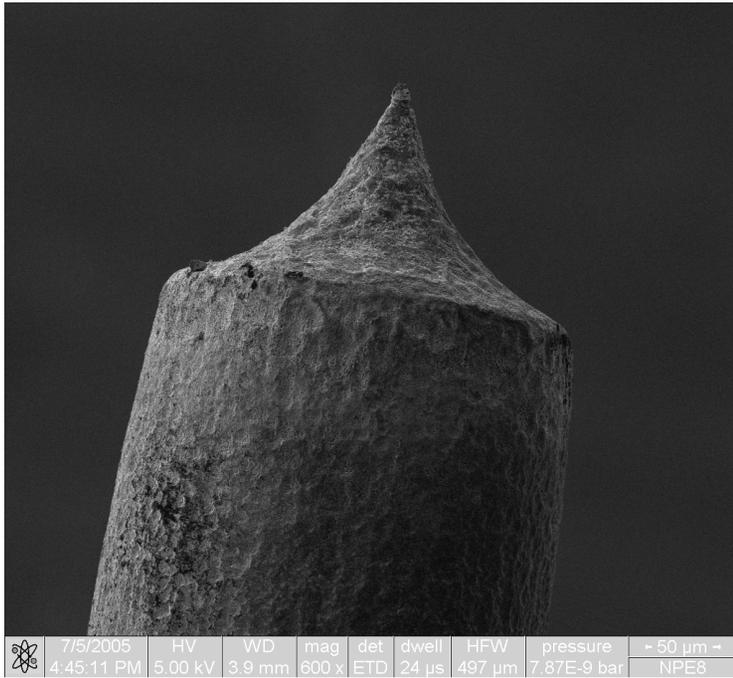
Bad interface?

# Future research

- ✓ Surface treatment for miscut substrates
- ✓ Measure the transport properties of LCMO strip for different angles relative to terraces
- ✓ Develop the sol-gel procedure for the growth of LCMO nanowires

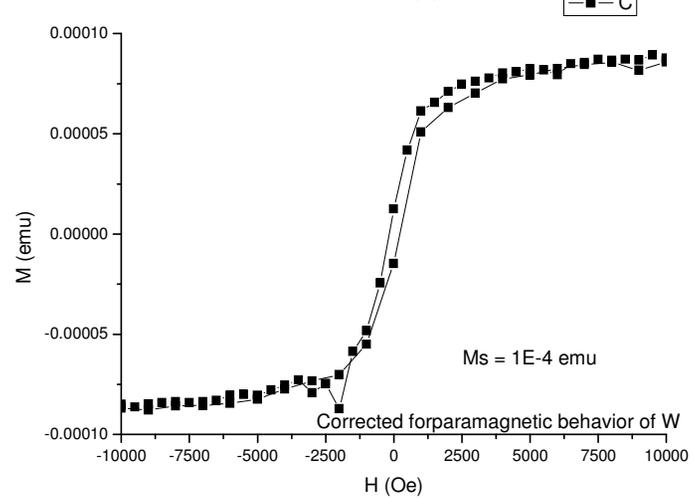
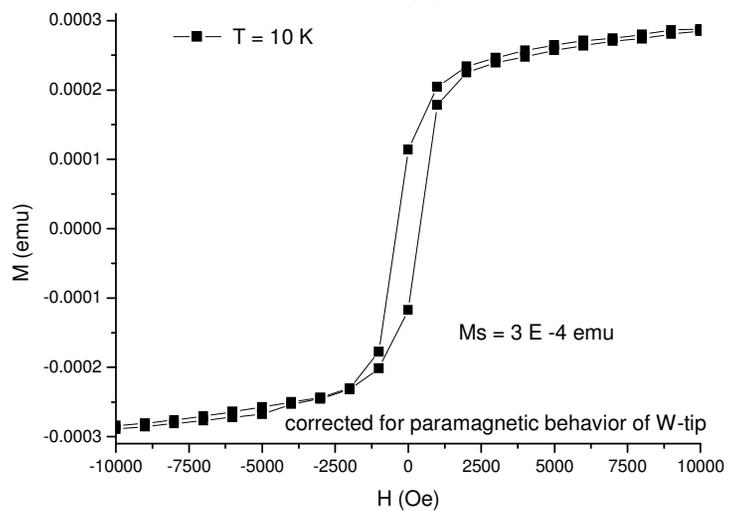
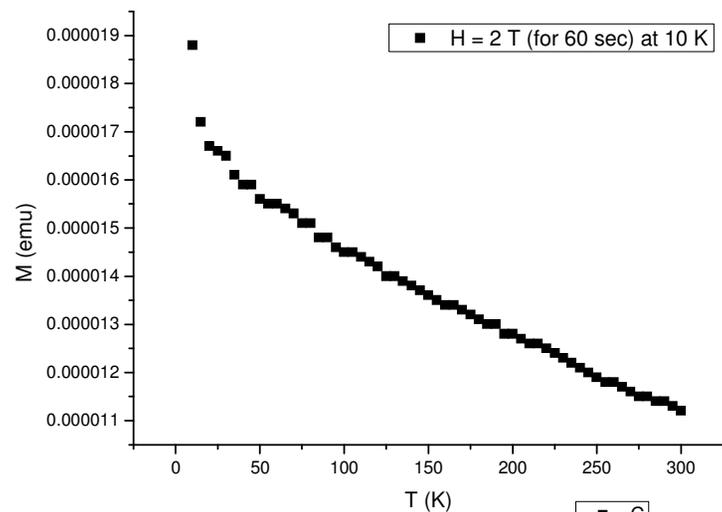
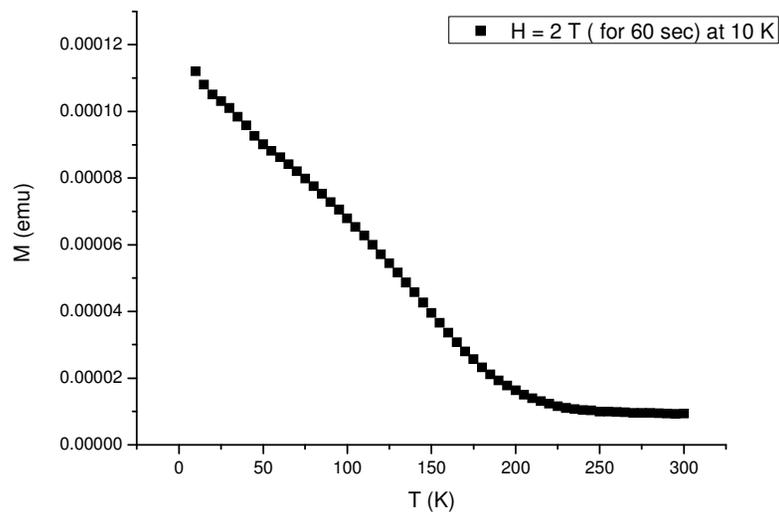


Tip radius of curvature  $\sim 136 \text{ nm}$   
Needle has same tree like surface as the coated tip (LCMO) suggesting LCMO only grows near the tip.



SEM imaging of LCMO ( $\text{La}_{0.67}\text{Ca}_{0.33}\text{MnO}_3$ ) coated W-tip  
 During sputtering cooling water was leaking into the vacuum, probably causing corrosion.  
 Expected layer thickness 25-50 nm (sputter rate 50nm/hour)

From images:  
 tip radius of curvature  $\sim 6 \mu\text{m}$  (before coating radius of curvature should be  $\sim 20 \text{ nm}$ )  
 roughness order of magnitude  $\sim 1 \mu\text{m}$



W-tip coated with LCMO

Bare W-tip